

The ISPlasma is held as part of the Expansion Program of the Second Stage Knowledge Cluster Initiative (Tokai Region Nanotechnology Manufacturing Cluster) to establish an Advanced Plasma Nanotechnology Science Research Foundation in the Tokai region. The symposium will include invited lectures, selected oral/poster presentations and panel discussions.

SCOPE

The Symposium focuses on advanced plasma science and technology and its applications for nitrides and nanomaterials. A list of categories is given below.

- **Plasma Science and Technology**
(Plasma Measuring Technology/Simulation/Etching Process/CVD Process/Solar Cells/Flexible Electronics/Plasma Applications)
- **Nitride Semiconductors**
(Crystal Growth/MBE Growth/Plasma Processing/Electronic Devices/White LEDs/UV LEDs)
- **Nanomaterials**
(Nanocarbon Materials/Solar Cells/Surface Modification/Surface Functionalization/Composite Materials/Functionally Graded Materials/Nanoparticles)
- **Integration Technology of Plasma Science, Nitride Semiconductors and Nanomaterials**
- **Industry-Academia-Government Collaboration**

SCHEDULE AT A GLANCE

3/ 7 (Sun)	Welcome Party at Student Hall in Meijo Univ.
3/ 8 (Mon)	Opening Technical Session Poster Session
3/ 9 (Tue)	Technical Session Panel Discussion "Application of Advanced Plasma Technology for Nitride Semiconductors" Poster Session Banquet at Meijo Cafeteria in Meijo Univ.
3/10 (Wed)	Technical Session Panel Discussion "Application Front of Advanced Plasma Science and Industry-Academia-Government Collaboration" Poster Session Closing

SPECIAL ISSUE

The deadline of the full paper submission is April 30th, 2010. After the review by the editorial board, whose accepted papers will be published in a special issue of Jpn. J. Appl. Phys. (JJAP). Please refer to the submission instructions provided on the website.

RELATED CONFERENCES

- **Int'l Conf. Plasma-Nanotechnology & Science (IC-PLANTS 2010)** (Mar. 11-12, 2010)
URL: <http://www.plasma.engg.nagoya-u.ac.jp/IC-2010/index.html>
- **7th Nitride Semiconductor Application Workshop** (Mar. 11, 2010)
URL: <http://www.isplasma.jp/english/17.html>
- **Grenoble Day (International Exchange with a Global Nanotechnology Center in France)** (Mar. 11, 2010)
URL: <http://www.isplasma.jp/english/17.html>

<http://www.isplasma.jp/>

Registration

- **Registration Fee:**
Early Registration (before January 31st, 2010) General : JPY 15,000 Student : JPY 3,000
Late Registration (until February 28th, 2010) General : JPY 20,000 Student : JPY 5,000
- **Banquet Fee (on March 9th)** General : JPY 5,000 Student : JPY 2,000
- * Banquet fees must be paid at the time of registration.

ACCESS

Centrair

(Central Japan International Airport)

To Downtown Nagoya

- By Train
• 25 min by "Meitetsu Express" to Kanayama Sta.
• 30 min by "Meitetsu Express" to Nagoya Sta.



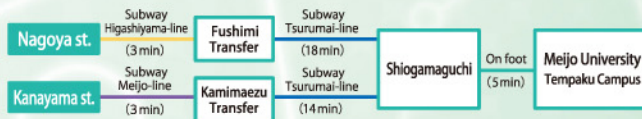
NARITA AIRPORT

To Nagoya Station

- By Train
1 hr. by "Narita Express" to Tokyo Sta.
→ 1 hr. 40 min by Shinkansen from Tokyo Sta.
- By Air
1 hr. 10 min to Centrair
→ 30 min by "Meitetsu Express" from Centrair

Meijo University Tempaku Campus

1-501 Shioigama-guchi, Tempaku-ku, Nagoya 468-8502, Japan
TEL +81-52-832-1151



Sightseeing



1 Nagoya Castle



2 Atsuta Shrine



3 Tokugawa En

<http://www.isplasma.jp/>



MEXT (Ministry of Education, Culture, Sports, Science and Technology)
Knowledge Cluster Initiative (The Second Stage)
-Tokai Region Nanotechnology Manufacturing Cluster-



ISPlasma2010

2nd International Symposium on Advanced Plasma Science and its Applications for Nitrides and Nanomaterials

March 7-10, 2010
Meijo University, Nagoya, Japan

Organizing Committee

Chairperson

Masaru Hori, Plasma Nanotechnology Research Center,
Nagoya University

Vice-Chairperson

Hideki Masuda, Nagoya Institute of Technology
Hiroshi Amano, Meijo University
Keiji Nakamura, Chubu University

Sponsored by :

Aichi Science & Technology Foundation

Co-sponsored by :

Aichi Prefecture, Nagoya City, Gifu Prefecture, Nagoya University, Nagoya Institute of Technology, Meijo University, Chubu University, The Japan Society of Applied Physics, The Japan Society of Plasma Science and Nuclear Fusion Research

Supported by :

The 162nd Committee on Wide Bandgap Semiconductor Photonic and Electronic Devices, Japan Society for the Promotion of Science, Mie Prefecture, Gifu University, Toyohashi University of Technology, Toyota Technological Institute, Mie University, Japan Fine Ceramics Center, National Institute for Fusion Science, Chubu Bureau of Economy Trade and Industry, Chubu Economic Federation, Nagoya Chamber of Commerce & Industry, Gifu Industries' Association, Nagoya Industrial Science Research Institute, Nagoya City Association for Industrial Technology, Nagoya Urban Industries Promotion Corporation, Gifu Research & Development Foundation, Chubu Industrial and Regional Advancement Center, Tokai Monodukuri Council, Greater Nagoya Initiative Center (GNIC), Aichi Industrial Research Association, Nagoya University Supportive Organization, Research Cooperation Association of NIT, Japan Society of Electromagnetic Wave Energy Applications (JEMEA), The Forum for Atomic and Molecular Data and their Applications

Grants :

Daiko Foundation, Research Foundation for the Electrotechnology of Chubu

Contact

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ISPlasma2010

PROGRAM AT A GLANCE

3/8 (Mon)

Plenary Speaker

S. Iijima (Meijo University, JAPAN)

Keynote/Invited/Knowledge Cluster Speakers

Plasma Science

U. Czarnetzki (Ruhr University, Bochum, GERMANY)
M. Hori (Nagoya University, JAPAN)
M. J. Kushner (University of Michigan, USA)
O. Takai (Nagoya University, JAPAN)

Nitride Semiconductors

H. Amano (Meijo University, JAPAN)
S. Arulkumaran (Nanyang Technological University, SINGAPORE)
T. Egawa (Nagoya Institute of Technology, JAPAN)
T. Fukuda (Tohoku University, JAPAN)
T. Hashizume (Hokkaido University, JAPAN)

Nanomaterials

T. Nozaki (Tokyo Institute of Technology, JAPAN)
J. Robertson (Cambridge University, UK)
Y. Watanabe (Nagoya Institute of Technology, JAPAN)
Y. Wu (National University of Singapore, SINGAPORE)

3/9 (Tue)

Keynote/Invited Speakers

Plasma Science

J. P. Chang (UC Los Angeles, USA)
M. Goeckner (University of Texas at Dallas, USA)

Nitride Semiconductors

Y. Cordier (CRHEA-CNRS, FRANCE)
B. Daudin (CEA Grenoble, FRANCE)
N. Grandjean (EPFL, SWITZERLAND)
U. K. Mishra (UC Santa Barbara, USA)
S. Noda (Kyoto University, JAPAN)
T. Uesugi (Toyota Central R&D Labs., Inc., JAPAN)

Nanomaterials

S. Fukuzumi (Osaka University, JAPAN)
M. Kogoma (Sophia University, JAPAN)
J. Patscheider (EMPA, SWITZERLAND)
T. Yoshida (Gifu University, JAPAN)

Panel Discussion

Application of Advanced Plasma Technology for Nitride Semiconductors

Moderator

Y. Nanishi (Ritsumeikan University, JAPAN)

Panelists

H. Amano (Meijo University, JAPAN)
B. Daudin (CEA Grenoble, FRANCE)
N. Grandjean (EPFL, SWITZERLAND)
T. Hashizume (Hokkaido University, JAPAN)
H. Kano (NU Eco Engineering Co., LTD., JAPAN)
U. K. Mishra (UC Santa Barbara, USA)
T. Okumura (Tokyo Metropolitan University, JAPAN)

3/10 (Wed)

Keynote/Invited Speakers

Plasma Science

R. d'Agostino (University of Bari, ITALY)
J. G. Han (CAPST, Sungkyunkwan University, KOREA)
U. R. Kortshagen (University of Minnesota, USA)
T. Takamoto (SHARP CORPORATION, JAPAN)
T. Yoshida (The University of Tokyo, JAPAN)

Nitride Semiconductors

V. Haerle (OSRAM, GERMANY)
K. Ota (TOYODA GOSEI Co., Ltd., JAPAN)
C. J. Sun (Industrial Technology Research Institute of Taiwan, TAIWAN)

Nanomaterials

P. Milani (The University of Milan, ITALY)
L. A. Rocha (University of Minho, PORTUGAL)

Industry-Academia-Government Collaboration

T. Higashi (Tokyo Electron Limited, JAPAN)
W. Izumiya (Sangyo Times, Inc., JAPAN)
E. Schultheiss (Fraunhofer Institute, GERMANY)

Panel Discussion

Application Front of Advanced Plasma Science and Industry-Academia-Government Collaboration

Moderator

W. Izumiya (Sangyo Times, Inc., JAPAN)

Panelists

M. Goeckner (University of Texas at Dallas, USA)
J. G. Han (CAPST, Sungkyunkwan University, KOREA)
M. Hori (Nagoya University, JAPAN)
S. Hosaka (Tokyo Electron Limited, JAPAN)
M. Sato (MARUBUN CORPORATION, JAPAN)
E. Schultheiss (Fraunhofer Institute, GERMANY)

3/7 (Sun)	
17:00	Registration
18:00	Welcome Party
19:30	

9:00	3/8 (Mon)		
	Registration		
	Opening		
	Plenary Speech		
	Coffee Break		
	Knowledge Cluster Initiative (The Second Stage) -Tokai Region Nanotechnology Manufacturing Cluster-		
12:00	Lunch		
13:00	Poster Session A		
14:30	Plasma 1 Advanced Plasma Measuring Technology and Plasma Science Technology	Nitride 1 Nitride Electronic Devices	Nanomaterials 1 Nanocarbon Materials I
	Coffee Break		
	Plasma 2 Simulation	Nitride 2 Growth of GaN and Related Materials	Nanomaterials 2 Nanocarbon Materials II
17:30	Poster Session A		

<http://www.isplasma.jp/>

3/9 (Tue)		
Registration		
Plasma 3 Etching Process I	Nitride 3 RF-MBE I	Nanomaterials 3 Solar Cells Based on Organic Materials
Coffee Break		
Plasma 4 Etching Process II	Nitride 4 RF-MBE II	Nanomaterials 4 Surface Modification/ Surface Functionalization
Lunch		
Poster Session B		
Nitride 5 Advanced Nitride Devices		
Coffee Break		
Nitride 6 Panel Discussion Application of Advanced Plasma Technology for Nitride Semiconductors		
Banquet		

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3/10 (Wed)		
Registration		
Plasma 5 CVD Process	Nitride 7 White LEDs	Nanomaterials 5 Composite/ Functionally Grade Materials
Coffee Break		
Plasma 6 Solar Cells Based on Plasma Science	Nitride 8 UV Devices	Nanomaterials 6 Nanoparticles
Lunch		
Poster Session B		
Plasma 7 Advanced Plasma Applications and Industry-Academia-Government Collaboration		
Coffee Break		
Plasma 8 Panel Discussion Application Front of Advanced Plasma Science and Industry-Academia-Government Collaboration		
Closing		

<http://www.isplasma.jp/>